

Static TOF-SIMS Surface Analysis of a CCl_2F_2 Activated Chromia Catalyst Used for a Cl/F Exchange Reaction

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Static TOF-SIMS results strongly underpin earlier conclusions from ESCA, XANES, and tracer studies that the accumulation of fluorine and chlorine at the surface of chromia by a heterogeneous reaction with a chlorofluorocarbon compound results in the formation of mixed chromium oxide halide species and not in the nucleation of CrCl_3 and/or CrF_3 phases.

TOF-SIMS is a highly sensitive surface analytical technique that probes only the (three) outermost layers of a sample. In the so-called static mode of SIMS, the measured signal originates only from a virgin surface. Therefore, the respective SIMS spectrum then comprises a strongly correlated fragmentation pattern of the original surface lattice.¹

It is well known that chromia needs to be halogenated before it becomes catalytically active in halogen exchange reactions. In several publications,^{2–5} it was concluded from ESCA, XANES, XRD, and tracer studies that, most probably, neither CrCl_3 nor CrF_3 but “chromium (III) oxide fluoride chloride” species are the catalytically active ones. However, additional independent experimental proof is required to underpin these conclusions.

In this study, static TOF-SIMS was used for the first time to answer the question of whether there are CrCl_3 and/or CrF_3 phases existing at the surface of chromia halogenated by exposure to CCl_2F_2 . Activated chromia as well as reference samples were analyzed by static TOF-SIMS.²

Cr_2O_3 was synthesized by a volcano reaction of $(\text{NH}_4)_2\text{Cr}_2\text{O}_7$. The primary reaction product was boiled in distilled water for 4 h, filtered, washed with distilled water, dried in air, and then heated at 400 °C for 3 h under N_2 . XRD proofed a structure according to PDF 38-1479.⁶ CrCl_3 was a commercial sample (Aldrich) delivered under Ar. XRD proofed a structure according to PDF 32-279.⁶ $\alpha\text{-CrF}_3$ was a commercial sample (Aldrich) delivered under Ar. XRD proofed a structure according to PDF 16-44.⁶ A halogenated but inactive catalyst was obtained after drying Cr_2O_3 in a 10 mL/min N_2 flow at 400 °C for 3 h and subsequent exposure to N_2 (10 mL/min) + CCl_2F_2 (2 mL/min) at 390 °C for 1 min in a tubular flow reactor. A halogenated and active catalyst was obtained after exposing dried chromia to N_2 (10 mL/min) + CCl_2F_2 (2 mL/min) at 390 °C for 120 min. A catalytically activated dismutation reaction of CCl_2F_2 was proofed by GC. The XPS surface compositions are found to be $\text{CrO}_{1.59}\text{F}_{0.04}\text{Cl}_{0.06}$ and $\text{CrO}_{1.26}\text{F}_{0.13}\text{Cl}_{0.17}$ for 1- and 120-min activated samples, respectively.² After exposure to CCl_2F_2 , halogenated chromia samples were taken from the reactor in a glovebox to avoid air exposure. They were transported to the TOF-SIMS instrument in an evacuated desiccator.

During transfer to the SIMS UHV spectrometer chamber, the samples were quickly exposed to air (a few seconds).

Static SIMS spectra were obtained by a TOF-SIMS IV instrument (Ion-Tof GmbH, Münster, Germany) with a pulsed Ga^+ primary ion beam (15 keV, 0.80 pA). This ion beam was digitally scanned over an analysis area of $200 \times 200 \mu\text{m}^2$. Total acquisition times were fixed to 50 s. Thus, the total ion dose was less than 6.0×10^{11} ions/ cm^2 (i.e., well below the static limit of SIMS ($\sim 1.0 \times 10^{13}$ ions/ cm^2)). Because of charging, low-energy electrons were used to stabilize the surface potential of the samples during analysis. The mass resolution at CrCl_4^- was ca. 7300. For more experimental details, see ref 2.

The negative static SIMS spectra of Cr_2O_3 , CrCl_3 , and $\alpha\text{-CrF}_3$ are displayed in Figures 1–3. Characteristic fragment ion patterns are obtained. Strong intensity was obtained for CrO_2^- and CrO_3^- with Cr_2O_3 , for CrCl_3^- and CrCl_4^- with CrCl_3 , and for CrF_3^- and CrF_4^- with CrF_3 . There are SIMS data for Cr_2O_3 in the literature^{1,7,8} reporting a very similar fragment CrO_x^- secondary ion pattern such as that in Figure 1. In the spectra of CrCl_3 and CrF_3 , some $\text{Cr}_x\text{O}_y\text{X}_z^-$ ($\text{X} = \text{Cl}, \text{F}$) secondary ions are found that might be due to the original existence of oxides in traces at the surface or/and due to partial hydration followed by hydrolysis of the samples during rapid exposure to air by the preparation. It should be mentioned that although all reference samples are characterized by Cr atoms octahedrally coordinated to their ligands the characteristic fragment ion patterns are somewhat different. These differences are due to the complexity of the secondary cluster ion formation process in SIMS. It is known that individual secondary ion emission probabilities and stabilities provide a substantial matrix effect in SIMS.¹

Negative TOF-SIMS spectra of Cr_2O_3 samples activated with CCl_2F_2 at 390 °C for 1 and 120 min are displayed in Figures 4 and 5, respectively. First, the high yields of CrX_4^- leading fragment ions found with the CrCl_3 and CrF_3 reference samples were not obtained for the activated chromia samples. The other CrX_n^- fragments ($n < 4$) are found again but with rather low yields. Moreover, secondary fragment ions such as Cr_2Cl_5^- , Cr_2Cl_6^- , Cr_2Cl_7^- , Cr_3Cl_7^- , Cr_3Cl_8^- , Cr_2F_5^- , Cr_2F_6^- , and Cr_2F_7^- , which were detected in the negative TOF-SIMS spectra of CrCl_3 and CrF_3 , respectively, were not observed in the activated chromia samples. These observations clearly indicate that separated CrCl_3 and/or CrF_3 phases are not present in significant

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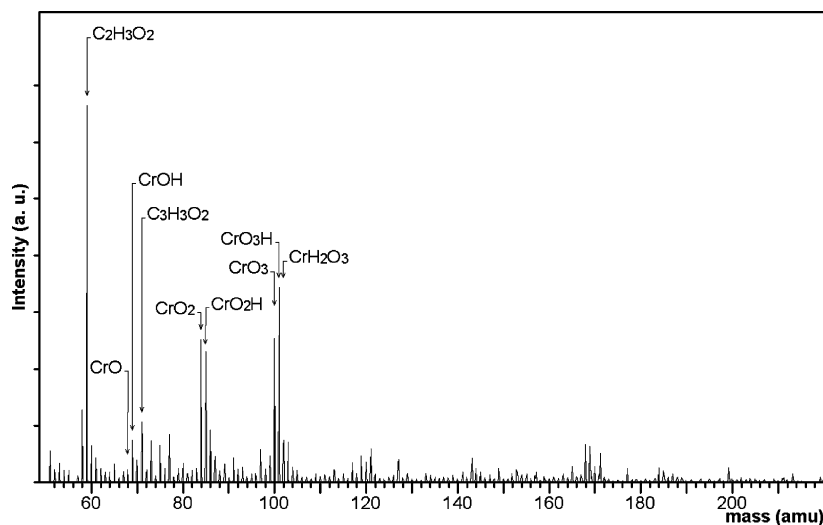


Figure 1. Negative TOF-SIMS spectrum of Cr_2O_3 .

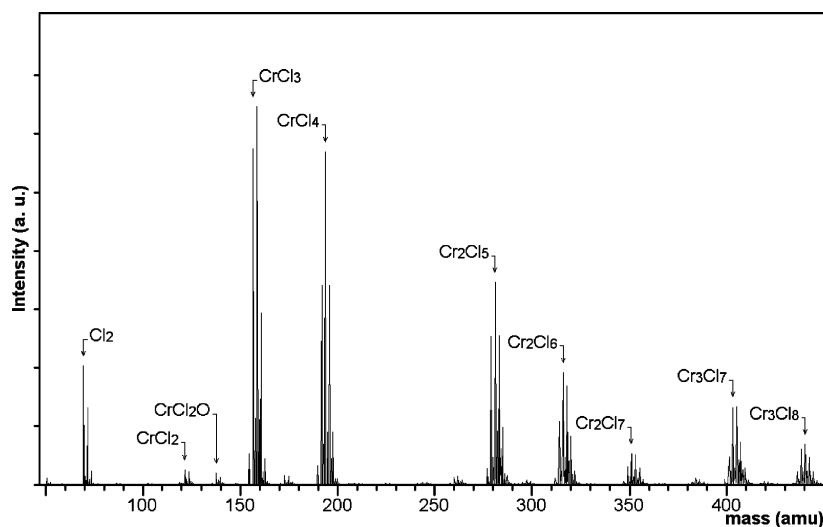


Figure 2. Negative TOF-SIMS spectrum of CrCl_3 .

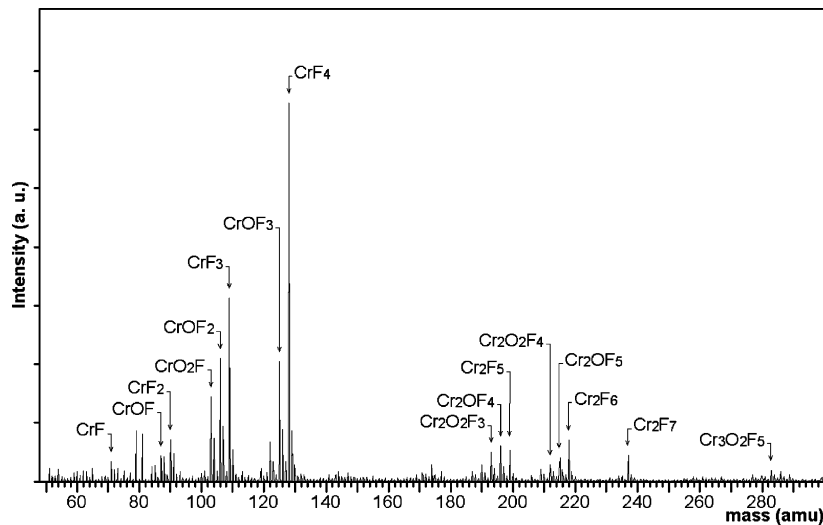


Figure 3. Negative TOF-SIMS spectrum of CrF_3 .

amounts on the surface. Instead, the results indicate that a mixed chromium oxide halide compound is formed during the activation process (e.g., by the exchange of some of the chromia oxygen atoms in the outermost layer with Cl and F atoms), in agreement with previous ESCA, XANES, and tracer studies.^{2–5} This interpretation is now strongly supported by our new SIMS

results because we found mixed secondary fragment ions such as CrClOF^- , CrClF_2^- , CrCl_2F^- , and $\text{Cr}_2\text{ClO}_2\text{F}^-$ exclusively in the spectra of activated chromia samples. These fragment ions are to be expected in a static SIMS experiment with a chromia surface where oxygen is statistically substituted by F and Cl, providing a neighborhood for Cr with O, Cl, and F.

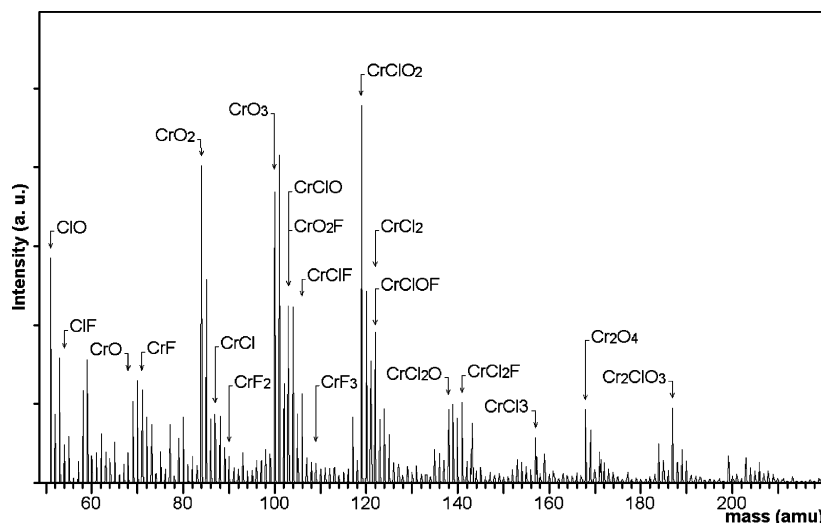


Figure 4. Negative TOF-SIMS spectrum of Cr_2O_3 after 1 min of activation in CCl_2F_2 at 390 °C.

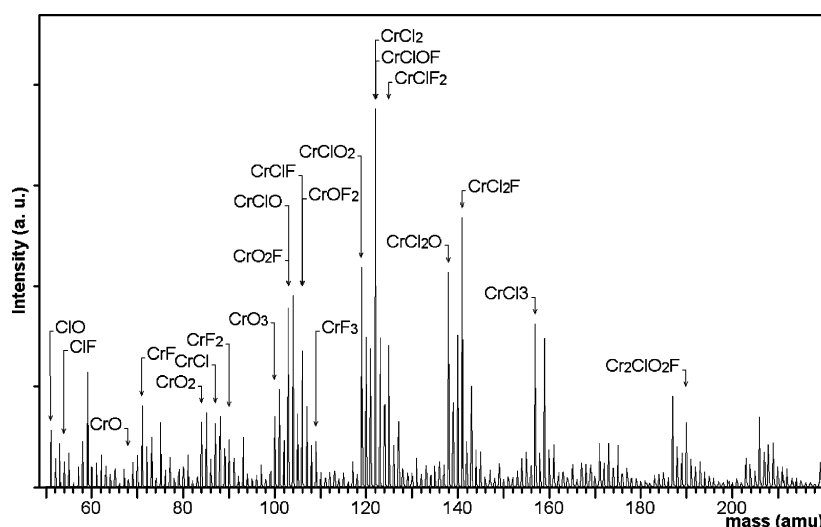


Figure 5. Negative TOF-SIMS spectrum of Cr_2O_3 after 120 min of activation in CCl_2F_2 at 390 °C.

Considering the SIMS spectrum of the chromia sample exposed to CCl_2F_2 for 1 min, high yields of CrO_2^- and CrO_3^- fragment ions can still be found. These high yields are also very characteristic of untreated chromia. They are substantially reduced in the spectrum of the 120-min activated chromia sample (i.e., vs increasing reaction time and halogenation). The conclusion is that at least after 1 min of activation in CCl_2F_2 nonreacted Cr_2O_3 regions still seem to exist at the sample's surface. These regions are consumed step by step by the heterogeneous halogenation reaction providing mixed $\text{CrO}_x\text{Cl}_y\text{F}_z$ species. Obviously, the secondary CrClO^- fragment ion seems to be the "key SIMS fragment" characteristic of these species. Accordingly, the CrClO^- yield increases with respect to increasing halogenation.

From the TOF-SIMS results presented in this communication, it can be concluded that the accumulation of fluorine and chlorine at the surface of chromia by a heterogeneous reaction with a chlorofluorocarbon results in the formation of chromium oxide halide species and not in the nucleation of CrCl_3 or CrF_3 phases. The observation of $\text{CrO}_x\text{Cl}_y\text{F}_z^-$ and $\text{CrCl}_x\text{F}_y^-$ secondary fragment ions for the activated samples in a static TOF-SIMS experiment is taken as a proof of that. The formation of separated CrX_3 ($\text{X} = \text{Cl}, \text{F}$) phases is not very probable because

the characteristic fragment ion patterns of these phases cannot be identified in the static TOF-SIMS spectra of activated chromia.

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References and Notes

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